

What is claimed is:

1. A method comprising:

providing a mask which includes:

an array of patterns, each of which
corresponds to a display device,

5 a window disposed between adjacent two
of said patterns,

placing a substrate to face said mask;

projecting an incident laser beam onto said
substrate through said window of said mask; and

10 determining a gap between said mask and
said substrate in a middle region of said
substrate in response to first and second
reflected beams, said first reflected beam being
generated by said incident laser beam reflected
15 by said mask, and said second reflected beam
being generated by said incident laser beam being
reflected by said substrate.

2. The method according to claim 1, further
comprising:

determining a deflection of said mask based
on said determined gap in said middle region.

3. The method according to claim 1, wherein
said mask further includes other windows disposed
around said array of said patterns, and

wherein said method further comprises:

5 projecting other incident laser beams onto
said substrate through said other windows;

 determining gaps between said mask and said
substrate near corners of said substrate in
response to third and fourth laser beams, said
10 third laser beams being generated by said other
incident laser beams being reflected by said mask,
and said fourth laser beams being generated by
said other incident laser beams being reflected
by said substrate, and

15 determining a deflection of said mask based
on said determined gap in said middle region and
said gaps near said corners.

4. The method according to claim 1, wherein
said patterns are arranged in a row.

5. The method according to claim 1, wherein
said patterns are arranged in rows and columns.

6. The method according to claim 1, wherein
said substrate is covered with a photo resist, a
portion of a main surface of said substrate being
exposed, and

5 said second reflected laser beam is
generated by said incident laser beam being

reflected by said exposed portion.

7. An proximity exposure method comprising:
providing a mask which includes:

an array of patterns, each of which
respectively corresponds to a display device,

5 a window disposed between adjacent two
of said patterns,

placing a substrate on a substrate stage
opposed to said mask;

projecting an incident laser beam onto said
10 substrate through said window of said mask; and

determining a gap between said mask and
said substrate in a middle region of said
substrate in response to first and second
reflected beams, said first reflected beam being
15 generated by said incident laser beam reflected
by said mask, and said second reflected beam
being generated by said incident laser beam being
reflected by said substrate; and

removing a deflection of said mask in
20 response to said determined gap in said middle
region.

8. The method according to claim 7, further
comprising:

projecting other incident laser beams onto

said substrate through said other windows;

5 determining gaps between said mask and said
substrate near corners of said substrate in
response to third and fourth laser beams, said
third laser beams being generated by said other
incident laser beams being reflected by said mask,
10 and said fourth laser beams being generated by
said other incident laser beams being reflected
by said substrate, and

 determining said deflection of said mask
based on said determined gap in said middle
15 region and said gaps near said corners.

9. The method according to claim 7, wherein
said removing includes:

 securing said mask and a glass plate to
form a sealed space between said mask and said
5 glass plate; and

 inflating or evacuating said sealed space
in response to said determined deflection.

10. The method according to claim 7, wherein
said determining said gap in said middle region
is executed every time said substrate is
exchanged.

11. The method according to claim 7, wherein

said determining said gap in said middle region
is executed every time said mask is exchanged.